

Supplementary information to:

**Regulating the Electron Density of Dual Transition Metal Sulfides  
Heterostructures for Highly Efficient Hydrogen Evolution in  
Alkaline Electrolytes**

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## ***Experimental Section***

### **Materials and chemicals**

NF was purchased from Shenzhen Green and Creative Environmental Science and Technology Co., Ltd. (Shenzhen, China). Hydrochloric acid (HCl), ethanol, carbon disulfide (CS<sub>2</sub>), and potassium hydroxide (KOH) were bought from Chongqing Chuandong Chemical Co., Ltd. (Chengdu, China). Ammonium molybdate tetrahydrate ((NH<sub>4</sub>)<sub>6</sub>Mo<sub>7</sub>O<sub>24</sub>·4H<sub>2</sub>O) and thiourea (CH<sub>4</sub>N<sub>2</sub>S) were purchased from Aladdin Co., Ltd. (shanghai, China). Ammonium fluoride (NH<sub>4</sub>F) was obtained from Greagent Co., Ltd. (shanghai, China). All reagents were used as received without any purification. Double distilled water (18.25 MΩ) was used throughout the experiments.

### **Preparation of NiMoO<sub>4</sub>·xH<sub>2</sub>O-NF precursor**

NiMoO<sub>4</sub>·xH<sub>2</sub>O-NF precursors were first synthesized through hydrothermal treatment with a modification.<sup>1</sup> A piece of commercial NF (2 cm × 3 cm) was washed ultrasonically in 3 M HCl solution, ethanol and DI water alternately for several minutes. In a typical synthetic procedure, 0.01 g NH<sub>4</sub>F and 0.155 g (NH<sub>4</sub>)<sub>6</sub>Mo<sub>7</sub>O<sub>24</sub>·4H<sub>2</sub>O were dissolved in 5 mL ultrapure water and 10 mL absolute alcohol under stirring at room temperature to form a uniform solution. Afterward, cleaned NF was placed in the uniform solution. Subsequently, the mixtures with a piece of as-treated NF were transferred into a Teflon-lined stainless steel autoclave (25 mL). Then autoclave was sealed and maintained at 150 °C for 8 h. After reactions

the products were washed with water and ethanol several times, and then dried to obtain  $\text{NiMoO}_4 \cdot x\text{H}_2\text{O}$  nanorods arrays on NF as precursor.

### **Preparation of hierarchical N-NiS/MoS<sub>2</sub>-NF heterostructures**

The  $\text{NiMoO}_4 \cdot x\text{H}_2\text{O}$ -NF precursor was placed at the center of a tube furnace. Thiourea power was put in another porcelain boat at the upstream side of the precursor. Subsequently, the furnace was increased to 500 °C under flowing inert atmosphere for 2 h. Then the furnace programmatically cooled to room temperature. The as-obtained sample was collected and washed with carbon disulfide and ethanol several times and then dried at 60 °C. The resulting product was denoted as N-NiS/MoS<sub>2</sub>-NF.

### **Preparation of NiS<sub>2</sub>/MoS<sub>2</sub>-NF**

The preparation of NiS<sub>2</sub>/MoS<sub>2</sub>-NF 3D electrode are similar to that of the N-NiS/MoS<sub>2</sub>-NF electrode except for replacing with S power as reactants.

### **Preparation of Pt/C-NF electrode**

10 mg commercial Pt/C (20 wt.%) and 50 μL Nafion solution (5 wt.%) were dispersed in water/ethanol solvent (500 μL distilled water and 450 μL ethanol) by 30 min sonication to form an ink. Then 200 μL catalyst ink was uniformly drop-cast onto the 1x1 cm<sup>2</sup> Ni foam and air-dried at room temperature.

### **Materials Characterization**

X-ray diffraction (XRD) patterns were recorded on a X'Pert Pro MPD , Holland. The morphologies of the materials were characterized using field-emission scanning

electron microscopy (FESEM), JEOL-7800F, Japan. High-resolution transmission electron microscopy (HR-TEM) images were recorded at FEI, TFI220, USA. The surface properties of the samples were investigated using X-ray photoelectron spectroscopy (XPS), Thermo ESCALAB 250XI, USA. The Raman of sample was characterized by Renishaw Invia, England.

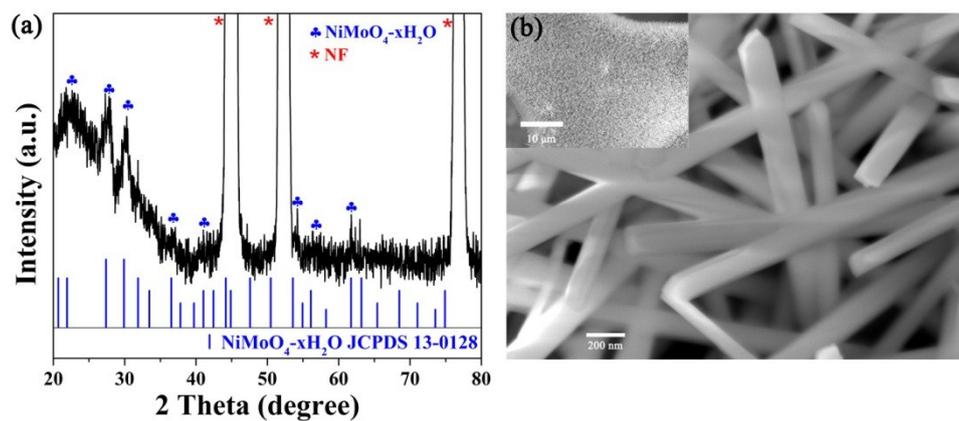
## **Electrochemical Measurements**

All electrochemical performance were tested in a typical three-electrode configuration on an electrochemical workstation (CHI 660E, CH Instruments, Inc., Shanghai, China). The as-obtained N-NiS/MoS<sub>2</sub>-NF was directly used as working electrode. Graphite rod and saturated calomel electrode (SCE) were used as counter and reference electrodes, respectively. All the potentials were calibrated to a reversible hydrogen electrode (RHE) with  $iR$  compensation. The HER polarization curves were obtained by linear sweep voltammetry (LSV) at a scan rate of 5 mV s<sup>-1</sup> in 1 M KOH. The electrochemical impedance spectroscopy (EIS) measurements were performed using an AC voltage with 5 mV amplitude in a frequency range from 100 kHz to 10 mHz under 1 M KOH solution. To estimate the electrochemically active surface area (ECSA) of the samples, cyclic voltammetry was applied to probe the electrochemical double-layer capacitance ( $C_{dl}$ ) at non-faradaic potentials in 1.0 M KOH at different scan rates.

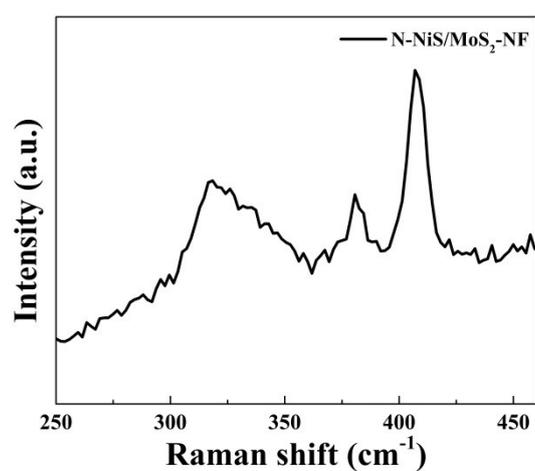
## **Theoretical basis**

Density function theory (DFT) calculations were performed using Dmol<sup>3</sup> code as implemented in the Materials Studios package of Accelrys.<sup>2,3</sup> The electron exchange-correlation potential was conducted by the generalized gradient approximation (GGA) with the Perdew-Burke-Ernzerhof (PBE) functional.<sup>4</sup> The semi-core pseudo potentials (DSPPs) combined with double numerical plus polarization (DNP) basis set were chosen for all of calculations.<sup>5</sup> The convergence tolerances were set to  $1.0 \times 10^{-5}$  hartree for energy change,  $2.0 \times 10^{-3}$  hartree  $\text{\AA}^{-1}$  for maximum force, and  $5.0 \times 10^{-3}$   $\text{\AA}$  for maximum displacement. The smearing was set to 0.005. The DFT correction (DFT-D) was used to treat the van der Waals interactions by TS method.<sup>6</sup> The Brillouin zone integration was sampled with the  $5 \times 5 \times 1$  k-point. The surface was simulated with a single-layer-thick p (3 $\times$ 3) plane slab with  $\sim 15$   $\text{\AA}$  vacuum.<sup>7</sup> Adsorption energy was calculated by subtracting the energies of gas phase species and clean surface from the total energy of the adsorbed system:

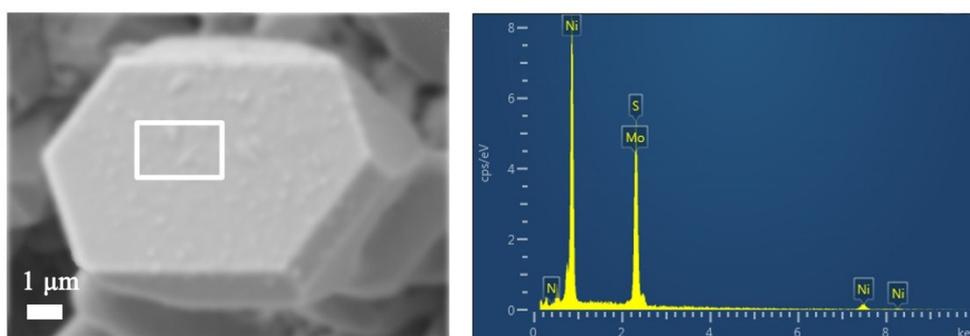
$E_{ads} = E_{adsorbate/slab} - [E_{adsorbate} + E_{slab}]$ . The hydrogen adsorption free energy ( $\Delta G_H$ ) was calculated as follows:  $\Delta G_H = \Delta E_H + \Delta ZPE - T\Delta S_H$ .



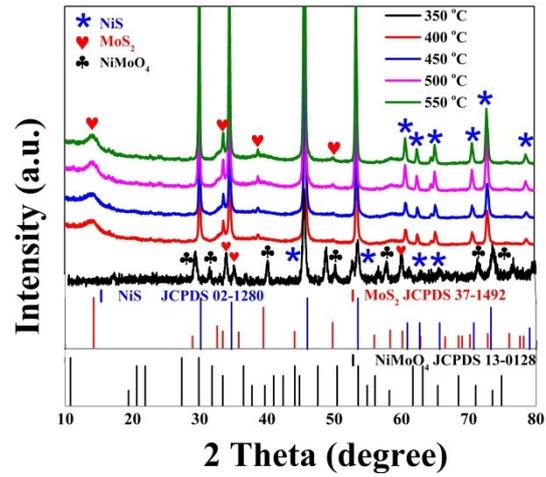
**Figure S1.** (a) XRD pattern and (b) SEM images of the precursor  $\text{NiMoO}_4 \cdot x\text{H}_2\text{O}$ -NF.



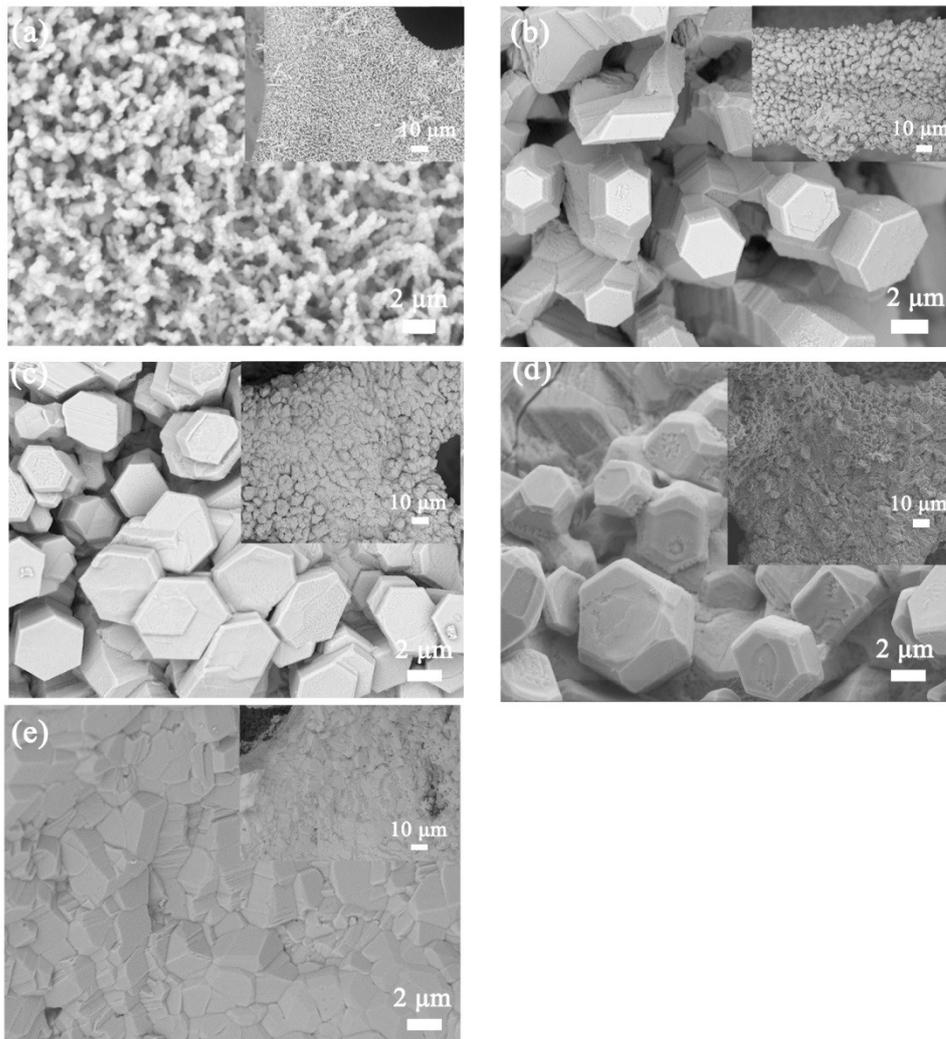
**Figure S2.** The Raman spectrum of N-NiS/MoS<sub>2</sub> heterostructures.



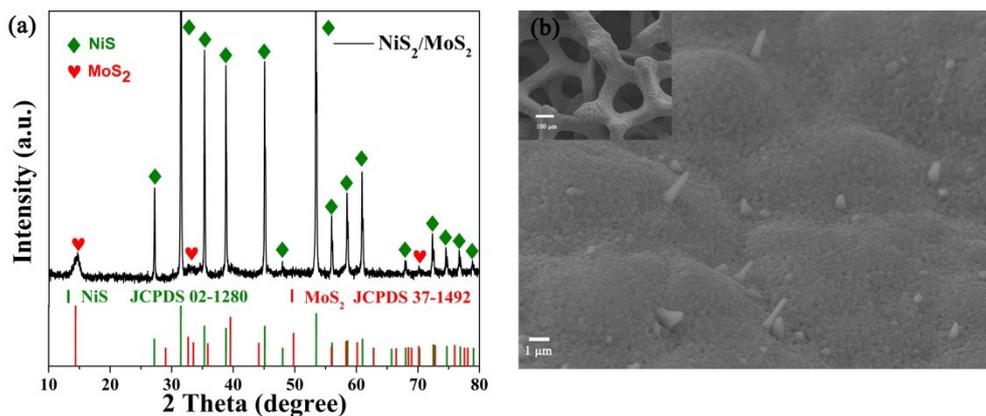
**Figure S3.** SEM-EDX patterns of N-NiS/MoS<sub>2</sub> heterostructures.



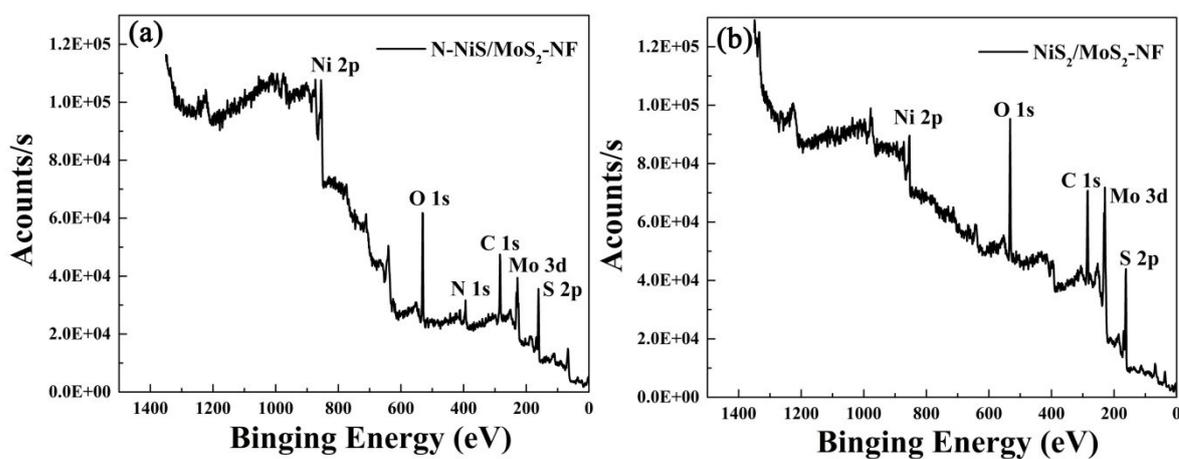
**Figure S4.** XRD patterns of the samples at different calcination temperature.



**Figure S5.** SEM images of the samples at different calcination temperature: (a) 350 °C, (b) 400 °C, (c) 450 °C, (d) 500 °C, and (e) 550 °C.

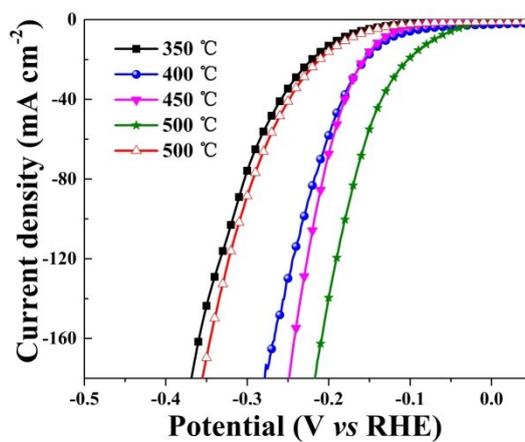


**Figure S6.** (a) XRD pattern and (b) SEM images of NiS<sub>2</sub>/MoS<sub>2</sub>-NF.

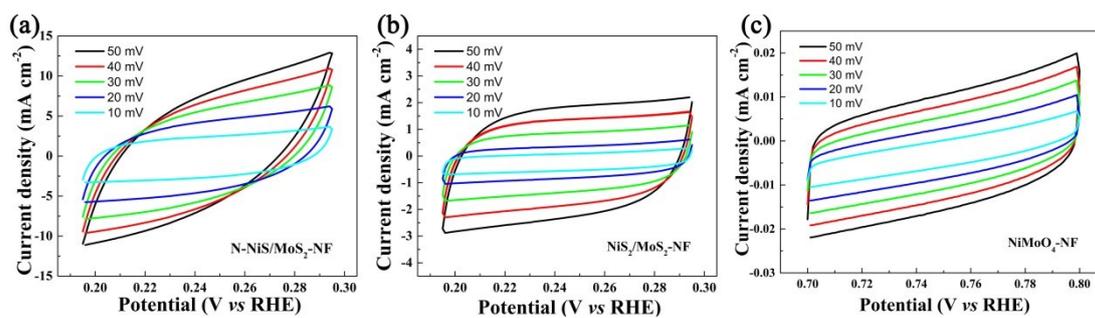


**Figure S7.** Surface composition and chemical state analyses of (a) N-NiS/MoS<sub>2</sub>-NF and (b)

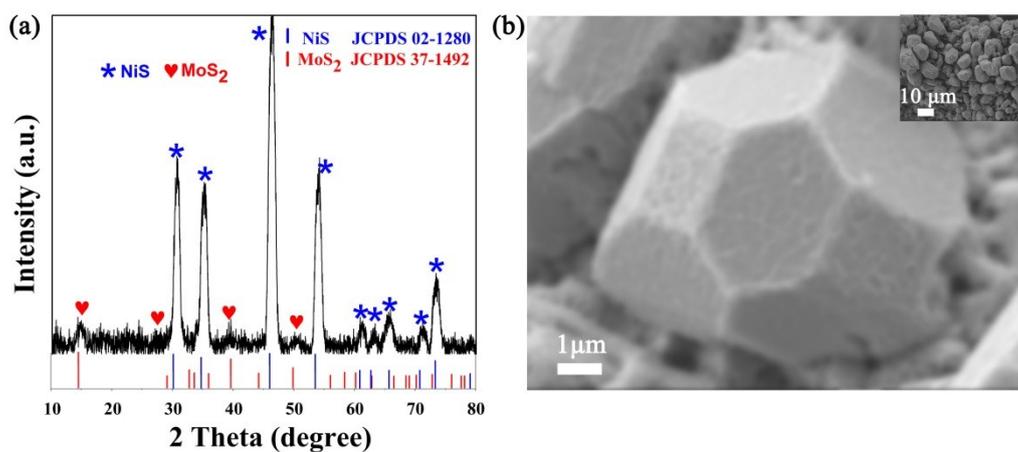
NiS<sub>2</sub>/MoS<sub>2</sub>-NF. XPS full spectrums.



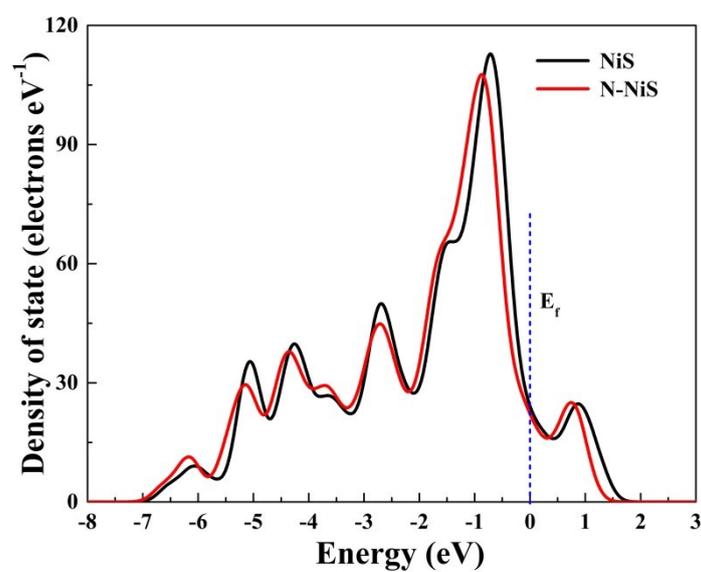
**Figure S8.** The LSV plots of N-NiS/MoS<sub>2</sub>-NF prepared at different temperatures.



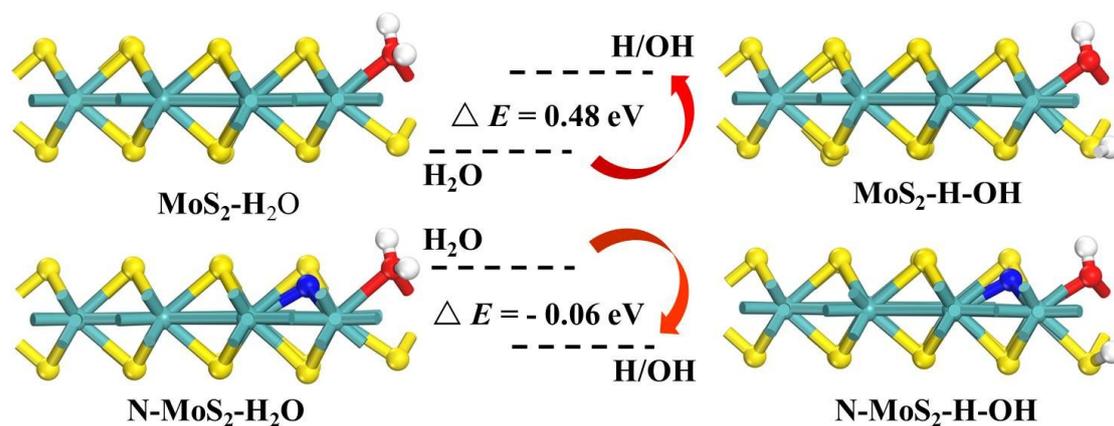
**Figure S9.** Cyclic voltammograms of (a) N-NiS/MoS<sub>2</sub>-NF, (b) NiS<sub>2</sub>/MoS<sub>2</sub>-NF, and (c) NiMoO<sub>4</sub>-NF in 1.0 M KOH at various scanning rates (from 5 to 30 mV S<sup>-1</sup>).



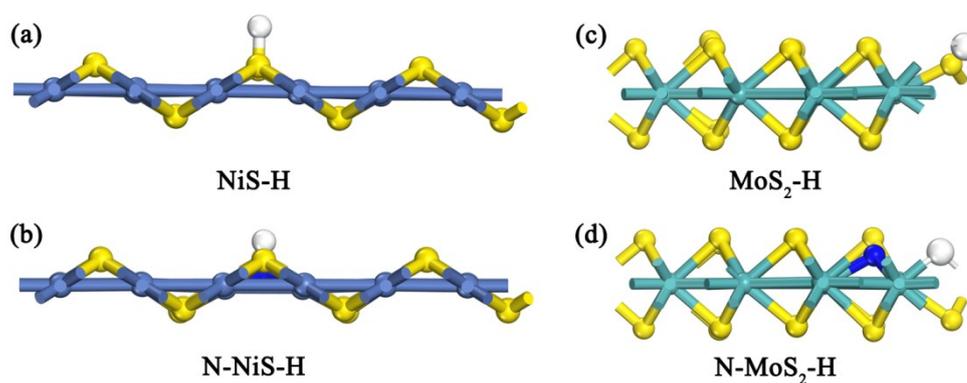
**Figure S10.** (a) XRD and (b) SEM images of N-NiS/MoS<sub>2</sub>-NF after stability test.



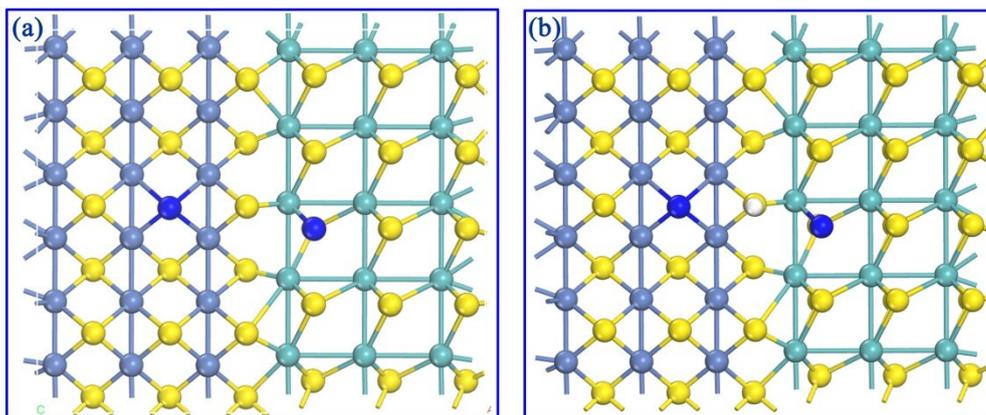
**Figure S11.** Calculated density of states for NiS and N-NiS. The Fermi Level is set at 0 eV.



**Figure S12.** Adsorbed  $\text{H}_2\text{O}$  dissociation configuration on the surfaces of  $\text{MoS}_2$  (002) facet and N- $\text{MoS}_2$  (002) facet, as well as corresponding dissociation energies in alkaline solution. Yellow, green, light blue, red and white balls represent S, Mo, N, O and H atoms, respectively.



**Figure S13.** Chemisorption models of  $\text{H}$  on the surfaces of (a)  $\text{NiS}$  (100), (b) N- $\text{NiS}$  (100), (c)  $\text{MoS}_2$  (002), and (d) N- $\text{MoS}_2$  (002). Yellow, dark blue, green, light blue and white balls represent S, Ni, Mo, N and H atoms, respectively.



**Figure S14.** (a) Schematic model of of N-NiS/MoS<sub>2</sub>; (b) Chemisorption models of H on the surfaces of of N-NiS/MoS<sub>2</sub>. Yellow, dark blue, green, light blue and white balls represent S, Ni, Mo, N and H atoms, respectively.

**Table S1.** Comparison of the HER electrocatalytic performance of N-NiS/MoS<sub>2</sub> catalysts with reported transition metals sulfide-based electrocatalysts in alkaline condition.

Catalysts	Current Density ( $j$ mA cm <sup>-2</sup> )	Overpotential at Corresponding $j$ (mV)	Tafel slope (mV/decade)	Reference
N-CoS <sub>2</sub> NW/CC	50	152	58	7
MoS <sub>2</sub> /Ni <sub>3</sub> S <sub>2</sub>	10	110	83	8
MoS <sub>2</sub> -Ni <sub>3</sub> S <sub>2</sub>	10	98	61	9
N-Ni <sub>3</sub> S <sub>2</sub> /NF	10	110	-	10
NiS <sub>2</sub> -MoS <sub>2</sub>	10	204	65	11
MoS <sub>2</sub> /NiS NCs	10	92	113	12
NiS/MoS <sub>2</sub> nanoflakes	10	117	58	13
N-Ni <sub>3</sub> S <sub>2</sub> /NF	10	155	113	14
Ni-Mo-S nanowire	100	290	103	15
MoS <sub>2</sub> /NiS yolk-shell microspheres	10	244	97	16
N-NiS/MoS <sub>2</sub> -NF	10	71	79	This work

**Table S2.** Binding energies of H<sub>2</sub>O on NiS and N-NiS substrates in alkaline solution.

	NiS (eV)	N-NiS (eV)
Binding Energies	-10.47	-10.83

## Reference

1. Y. Y. Chen, Y. Zhang, X. Zhang, T. Tang, H. Luo, S. Niu, Z. H. Dai, L. J. Wan and J. S. Hu, *Adv. Mater.*, 2017, **29**, 1703311.
2. B. Delley, *J. Chem. Phys.*, 2000, **113**, 7756-7764.
3. B. Delley, *J. Chem. Phys.*, 1990, **92**, 508-517.
4. J. P. Perdew, K. Burke and M. Ernzerhof, *Phys. Rev. Lett.*, 1996, **77**, 3865-3868.
5. B. Delley, *Phys. Rev. B*, 2002, **66**, 155125.
6. A. Tkatchenko and M. Scheffler, *Phys. Rev. Lett.*, 2009, **102**, 073005.
7. P. Z. Chen, T. P. Zhou, M. L. Chen, Y. Tong, N. Zhang, X. Peng, W. S. Chu, X. J. Wu, C. Z. Wu and Y. Xie, *ACS Catal.*, 2017, **7**, 7405-7411.
8. J. Zhang, T. Wang, D. Pohl, B. Rellinghaus, R. Dong, S. Liu, X. Zhuang and X. Feng, *Angew. Chem. Int. Ed.*, 2016, **55**, 6702-6707.
9. Y. Yang, K. Zhang, H. Lin, X. Li, H. C. Chan, L. Yang and Q. Gao, *ACS Catal.*, 2017, **7**, 2357-2366.
10. P. Chen, T. Zhou, M. Zhang, Y. Tong, C. Zhong, N. Zhang, L. Zhang, C. Wu and Y. Xie, *Adv. Mater.*, 2017, **29**, 1701584.
11. P. Kuang, T. Tong, K. Fan and J. Yu, *ACS Catal.*, 2017, **7**, 6179-6187.
12. Z. J. Zhai, C. Li, L. Zhang, H. C. Wu, L. Zhang, N. Tang, W. Wang and J. L. Gong, *J. Mater. Chem. A*, 2018, **6**, 9833-9838.
13. K. Y. Tao, Y. Gong and J. H. Lin, *Electrochimica Acta*, 2018, **274**, 74-83.
14. T. Y. Kou, T. Smart, B. Yao, I. Chen, D. Thota, Y. Ping and Y. Li, *Adv. Energy Mater.*,

2018, **8**, 1703538.

15. Z. Ma, H. Meng, M. Wang, B. Tang, J. Li and X. Wang, *ChemElectroChem*, 2018, **5**, 335-342.
16. Q. Qin, L. Chen, T. Wei and X. Liu, *Small*, 2018, 1803639.